



Atty. Dkt. No.	M#	Client Ref.
081468	0309196	P-1851.000-US
Applicant: Aleksey Yurievich KOLESNYCHENKO, et al.		
Appln. No.: 10/823,777		
Filing Date: April 14, 2004		
Examiner: GUTIERREZ, Kevin C.		Group Art Unit: 2851

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	ER 2004/0180294 A1	09/2004	Baba-Ali et al.			
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	VR 2006/0238730	10/2006	Nei et al.			

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							Enclosed	No	Enclose	No
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	XR	JP A 57-153433	09/1982	Japan	Takanashi et al.	X				
	YR	JP A 59-19912	02/1984	Japan	Kawamura et al.	X				
	ZR	JP A 05-62877	03/1993	Japan	Shinohara	X				
	AAR	JP A 08-316125	11/1996	Japan	Rudorfu et al.	X				

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	FFR 2005/0036213 A1	02/2005	Mann et al.			
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YYR					
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AAAR					

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	CCCR	WO 2004/077154 A1	09/2004	PCT	Babi-Ali et al.	X			
	DDDR	WO 2004/081666 A1	09/2004	PCT	Rolland et al.	X			
	EEER	WO 2004/090577 A2	10/2004	PCT	Binnard	X			
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	WWWR	WO 2005/034174 A2	04/2005	PCT	Caroll	X			
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	YYR	WO 2005/054955 A2	06/2005	PCT	Streekerk et al.	X			
	ZZR	WO 2005/062128 A2	07/2005	PCT	Lyons et al.	X			
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	HHHHR					
	IIIIIR					
	JJJJR					
	KKKKR					
	LLLLR					
	MMMMR					
	NNNNR					
	OOOOR					
	PPPPR					

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					Enclosed	No
	QQQQR					
	RRRRR					
	SSSSR					

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	TTTTT	Emerging Lithographic Technologies VI, Proceedings of SPIE, vol. 4688 (2002), "Semiconductor Foundry, Lithography, and Partners", B.J. Lin, pages 11-24.		
	UUUUR	Optical Microlithography XV, Proceedings of SPIE, vol. 4691 (2002), "Resolution Enhancement of 157 nm Lithography by Liquid Immersion", M. Switkes et al., pages 459-465.		
	VVVVR	J. Microolith., Microfab., Microsyst., vol. 1 No. 3, October 2002, Society of Photo-Optical Instrumentation Engineers, "Resolution enhancement of 157 nm lithography by liquid immersion", M. Switkes et al., pages 1-4.		
	WWWWW	Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (2003), "Immersion lithography; its potential performance and issues", Solchi OWA et al., pages 724-733.		
	XXXXR	Information Disclosure Statement dated Oct. 19, 2006 for US Application No. 11/473,147		
	YYYYR	Non-Final Office Action, dated Mar. 20, 2007, issued for US Application No. 11/473,147		

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